

APPARATUS AND METHOD FOR CLEANING SEMICONDUCTOR SUBSTRATES

ABSTRACT OF THE DISCLOSURE

5 An apparatus for cleaning semiconductor substrates includes a
chamber having a cleaning room and a drying room disposed over the
cleaning room. The cleaning room and the drying room are separated or
placed in communication with one another by a separation plate. An
exhaust path is formed at a central portion of the separation plate. As de-
10 ionized water (DI water) filling the cleaning room is drained during a dry
process, the inside of the drying room is decompressed, and a drying
fluid in the drying room flows from the drying room to the cleaning
room along the exhaust path.